

BAY AREA AIR QUALITY MANAGEMENT DISTRICT
Best Available Control Technology (BACT) Guideline

Source Category

Source:	<i>Semiconductor Fabrication - Photoresist Operations</i>	Revision:	2
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Class:	All	Date:	06/16/95

Determination

POLLUTANT	BACT 1. Technologically Feasible/ Cost Effective 2. Achieved in Practice	TYPICAL TECHNOLOGY
POC	1. n/d 2. Enclosure of photoresist track and spinner, and vent to abatement system w/ destruction/recovery efficiency $\geq 98.5\%$ or VOC outlet concentration ≤ 10 ppmv ^{a,b,T}	1. n/d 2. BAAQMD approved Collection System and Abatement Device ^{a,b,T}
NOx	1. n/a 2. n/a	1. n/a 2. n/a
SO ₂	1. n/a 2. n/a	1. n/a 2. n/a
CO	1. n/a 2. n/a	1. n/a 2. n/a
PM ₁₀	1. n/a 2. n/a	1. n/a 2. n/a
NPOC	1. n/d 2. Same as for POC above ^{a,b,T}	1. n/d 2. BAAQMD approved Collection system and Abatement Device ^{a,b,T}

References

<p>a. BAAQMD A #6266 b. For abatement device, the following are acceptable: ≤ 10 ppmv at outlet; or $\geq 98.5\%$ destruction/recovery efficiency if inlet VOC ≥ 2000 ppmv; or $\geq 97\%$ efficiency if inlet VOC ≥ 200 to < 2000 ppmv; or $\geq 90\%$ efficiency if inlet VOC < 200 ppmv. T. TBACT</p>
